Title (en)

POLISHING PAD

Title (de)

POLIERKISSEN

Title (fr)

TAMPON DE POLISSAGE

Publication

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Application

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Abstract (en)

[origin: WO2009025748A1] The invention provides a polishing pad comprising a polishing layer having a polishing surface comprising plurality of grooves disposed into the polishing layer a measurable depth from the polishing surface, and a barrier region free of grooves, and a transparent window disposed in and surrounded by the barrier region.

IPC 8 full level

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